

SAMPLE HEIGHT ADJUSTING DEVICE

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Abstract

PROBLEM TO BE SOLVED: To provide a sample height adjusting device which can easily perform focusing.

SOLUTION: This device is provided with a laser beam irradiating means 4 by which a sample 1 is irradiated with a laser beam 14 not in parallel to the height adjustment direction of the sample, a long-focus optical microscope 5 on which the reflected light 15 of the laser beam 14 is made incident, and sample moving means 6 and 7 which find the position of the sample 1 in the height direction according to the incidence position of the reflected light on the optical microscope 5 and move the sample in the height direction according to the height-directional position. Through this constitution, the height variation quantity of the sample is found from the displacement quantity of the reflected light in the optical microscope 5 and the height of the sample is adjusted according to the height variation quantity to easily put an incidence beam system in focus.

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